

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Won-Sung Choi)
 Serial No: 09/726,977) Art Unit 1763
 Filed: November 30, 2000)
 For: THIN FILM DEPOSITION APPARATUS) Examiner
 FOR SEMICONDUCTOR) Kackar, Ram N.

Commissioner for Patents
 Washington, D.C. 20231

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Sir:

In response to the Office action dated April 16, 2002, please amend the above-identified application as follows:

IN THE CLAIMS

Please cancel claim 4, without prejudice.

Please replace claims 1, 2, 5 and 11 with the following claims rewritten in clean form:

1. (Amended) A semiconductor thin film deposition apparatus comprising:
 at least one reactor in which a wafer is received;
 a gas supply portion for supplying a reaction gas or inert gas to the reactor, wherein
 the gas supply portion includes:
 at least one reaction gas supply unit for selectively providing the reaction
 gas to the reactor; and
 an inert gas supply unit for providing the inert gas to the reactor;
 an exhaust pump for exhausting gas from the reactor; and
 an ozone supply portion for generating ozone to react with the reaction gas,
 wherein the ozone supply portion includes:
 an ozone generator for generating the ozone;
 at least one ozone transfer unit for transferring ozone to the reactor; and